

INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.00840102	Serial No.: 10/770,797
	Applicant(s): Yates et al.	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed: April <u>26</u> , 2004	

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>W</i>		3,968,565	07/13/76	Bertens et al.			
		5,545,289	08/13/96	Chen et al.			
		5,741,368	04/21/98	Sahbari			
		5,780,359	07/14/98	Brown et al.			
		5,811,022	09/22/98	Savas et al.			
		5,851,302	12/22/98	Solis			
		5,876,903	03/02/99	Ng et al.			
		5,891,803	04/06/99	Gardner			
		6,063,712	05/16/00	Gilton et al.			
		6,162,738	12/19/00	Chen et al.			
<i>W</i>		6,703,319	03/09/04	Yates et al.			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
<i>W</i>		0662705 A2	12/29/94	Europe				
		0773480 A1	11/13/96	Europe				
		411067703	03/9/99	Japan				
<i>W</i>		WO 99/45443	09/10/99	PCT				

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
<i>W</i>		"Material Safety Data Sheet for PRX-407 [®] ", Silicon Valley Chemlabs, Inc., Sunnyvale, VA 94086, 1998:4 pgs.

EXAMINER <i>W</i>	Date Considered <i>5/24/07</i>
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609: Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed: April 26, 2004	

Examiner Initial	Copy Enclosed	Document Description
		"Material Safety Data Sheet", Shipley, <i>PRX-407 Advanced Plasma Etch Polymer Remover</i> , July 26, 2000:7 pgs.
		Product information for: PRX-407 [®] Advanced Plasma Etch Polymer Remover, Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086, 1998
		"Post-Etch SWP Removal," SVC Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086:5 pgs.
		"Product Selection Guide," SVC Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086:2 pgs
		Sotoaka et al., "Cleaning solvent for manufacturing semiconductor element and semiconductor element using the same," English Abstract of JP 411067703 A:1 pg.

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INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.00840102	Serial No.: 10/770,797
	Applicant(s): Yates et al.	Confirmation No.: 1476
	Application Filing Date: February 3, 2004	Group: 1751
	Information Disclosure Statement mailed: February 28, 2007	

U.S. PATENT DOCUMENTS


Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
		None					

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
M	X	WO 98/40338	17 September 1998	PCT				

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
		None

EXAMINER 	Date Considered 5/24/07
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	